

	Hit s	Search Text	DBs
1	3	(hard near5 mask\$3) and capacitor and ((photosensitive near5 sol\$3gel) or ((titanium or Ti) near7 sol\$3gel) or (Ti\$2Al near5 organic near4 gel) or (titanium near3 alumin\$3 near4 sol\$3gel)) and ((photoresist or resist or photo\$3cur\$4 or (radiation near5 sensitive)) same (pattern\$3 or expos\$3 or illuminat\$3 or irradiat\$3)) and ((thermal\$3 near5 (decompos\$5 or treat\$5)) or heat\$4 or bak\$4) and (etch\$3 same pattern\$3 same ((hard near5 mask) or (etch\$3resist\$3 near5 mask\$3)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
2	3	capacitor and ((photosensitive near5 sol\$3gel) or ((titanium or Ti) near7 sol\$3gel) or (Ti\$2Al near5 organic near4 gel) or (titanium near3 alumin\$3 near4 sol\$3gel) or TiOEt ) and ((photoresist or resist or photo\$3cur\$4 or (radiation near5 sensitive)) same (pattern\$3 or expos\$3 or illuminat\$3 or irradiat\$3)) and ((thermal\$3 near5 (decompos\$5 or treat\$5)) or heat\$4 or bak\$4) and (etch\$3 same pattern\$3 same ((hard near5 mask) or (etch\$3resist\$3 near5 mask\$3)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

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3	96	capacitor and (((photosensitive near5 sol\$3gel) or ((titanium or Ti) near7 sol\$3gel) or (Ti\$2Al near5 organic near4 gel) or (titanium near3 alumin\$3 near4 sol\$3gel) or TiOEt or TEOS) same (photoresist or resist or photo\$3cur\$4 or (radiation near5 sensitive)) same (pattern\$3 or expos\$3 or illuminat\$3 or irradiat\$3)) and ((thermal\$3 near5 (decompos\$5 or treat\$5)) or heat\$4 or bak\$4) and (etch\$3 same pattern\$3 same ((hard near5 mask) or (etch\$3resist\$3 near5 mask\$3)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
4	60	capacitor and ((photosensitive near5 sol\$3gel) or ((titanium or Ti) near7 sol\$3gel) or (Ti\$2Al near5 organic near4 gel) or (titanium near3 alumin\$3 near4 sol\$3gel) or TiOEt or sol\$4gel) and ((photoresist or resist or photo\$3cur\$4 or (radiation near5 sensitive)) same (pattern\$3 or expos\$3 or illuminat\$3 or irradiat\$3)) and ((thermal\$3 near5 (decompos\$5 or treat\$5)) or heat\$4 or bak\$4) and (etch\$3 same pattern\$3 same ((hard near5 mask) or (etch\$3resist\$3 near5 mask\$3)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

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5	3	<p>capacitor and</p> <p>((photosensitive near5 sol\$3gel) or ((titanium or Ti) near7 sol\$3gel) or (Ti\$2Al near5 organic near4 gel) or (titanium near3 alumin\$3 near4 sol\$3gel) or TiOEt or sol\$4gel) same (photoresist or resist or photo\$3cur\$4 or (radiation near5 sensitive))</p> <p>same (pattern\$3 or expos\$3 or illuminat\$3 or irradiat\$3))</p> <p>and ((thermal\$3 near5 (decompos\$5 or treat\$5)) or heat\$4 or bak\$4) and (etch\$3 same pattern\$3 same ((hard near5 mask) or (etch\$3resist\$3 near5 mask\$3)))</p>	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
6	3	<p>capacitor and</p> <p>((photosensitive near5 sol\$3gel) or ((titanium or Ti) near7 sol\$3gel) or (Ti\$2Al near5 organic near4 gel) or (titanium near3 alumin\$3 near4 sol\$3gel) or TiOEt or sol\$4gel) same (photoresist or resist or photo\$3cur\$4 or (radiation near5 sensitive)))</p> <p>and (pattern\$3 or expos\$3 or illuminat\$3 or irradiat\$3) and</p> <p>((thermal\$3 near5 (decompos\$5 or treat\$5)) or heat\$4 or bak\$4) and (etch\$3 same pattern\$3 same ((hard near5 mask) or (etch\$3resist\$3 near5 mask\$3)))</p>	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

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7	47	capacitor and (((photosensitive near5 sol\$3gel) or ((titanium or Ti) near7 sol\$3gel) or (Ti\$2Al near5 organic near4 gel) or (titanium near3 alumin\$3 near4 sol\$3gel) or TiOEt or sol\$4gel) same (photoresist or resist or photo\$3cur\$4 or (radiation near5 sensitive))) and (pattern\$3 or expos\$3 or illuminat\$3 or irradiat\$3) and ((thermal\$3 near5 (decompos\$5 or treat\$5)) or heat\$4 or bak\$4) and (etch\$3 same (pattern\$3 or mask\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
8	1	(capacitor or (dielectric same top same bottom same electrode)) and ((photosensitive near5 sol\$3gel) or ((titanium or Ti or Al or alumin\$2m) near6 organic near3 sol\$3gel)) and (mask near4 (hard or etch\$4resist\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
9	6	(capacitor or (dielectric same top same bottom same electrode)) and ((photosensitive near5 sol\$3gel) or ((titanium or Ti or Al or alumin\$2m) near6 organic near3 sol\$3gel))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
10	5	(capacitor or (dielectric same top same bottom same electrode)) and ((photosensitive near5 sol\$3gel) or ((titanium or Ti) near6 organic near3 sol\$3gel))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

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11	95	(capacitor or (dielectric same top same bottom same electrode)) and ((photosensitive near5 sol\$3gel) or ((titanium or Ti or Al or alumin\$2m) same (organic near8 sol\$3gel)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
12	1	(capacitor or (dielectric same top same bottom same electrode)) and ((photosensitive near5 sol\$3gel) or ((titanium or Ti or Al or alumin\$2m) same (organic near8 sol\$3gel))) and ((gel or sol\$4gel) same photosensitive same (mask or hard\$4mask or (etch\$4resist\$4 near6 mask)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
13	1	(capacitor or (dielectric same top same bottom same electrode)) and ((photosensitive near5 sol\$3gel) or ((titanium or Ti or Al or alumin\$2m) same (organic near8 sol\$3gel))) and ((gel or sol\$4gel) same (photosensitive or (light near8 sensitiv\$4)) same (mask or hard\$4mask or (etch\$4resist\$4 near6 mask)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
14	52	((gel or sol\$4gel) same (photosensitive or (light near8 sensitiv\$4)) same (mask or hard\$4mask or (etch\$4resist\$4 near6 mask)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

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15	18	((organic or polymer\$4) same (gel or sol\$4gel) same (photosensitive or (light near8 sensitiv\$4)) same (mask or hard\$4mask or (etch\$4resist\$4 near6 mask)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
16	22	((organic or polymer\$4 or organometal\$3) same (gel or sol\$4gel) same (photosensitive or (light near8 sensitiv\$4)) same (mask or hard\$4mask or (etch\$4resist\$4 near6 mask)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
17	75	(capacitor or (dielectric same top same bottom same electrode)) and (((photosensitive or organometallic) near5 sol\$3gel) or ((titanium or Ti or Al or alumin\$2m) same (organic near8 sol\$3gel))) and (mask or pattern)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
18	47	capacitor and (((photosensitive or organometal\$4) near5 sol\$3gel) or ((titanium or Ti) near7 sol\$3gel) or (Ti\$2Al near5 organic near4 gel) or (titanium near3 alumin\$3 near4 sol\$3gel) or TiOEt or sol\$4gel) same (photoresist or resist or photo\$3cur\$4 or (radiation near5 sensitive)) and (pattern\$3 or expos\$3 or illuminat\$3 or irradiat\$3) and ((thermal\$3 near5 (decompos\$5 or treat\$5)) or heat\$4 or bak\$4) and (etch\$3 same (pattern\$3 or mask\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

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19	43	(capacitor or (dielectric same top same bottom same electrode)) and (((photosensitive or organometallic) near5 sol\$3gel) or ((titanium or Ti or Al or alumin\$2m) same (organic near8 sol\$3gel))) and (mask or pattern) and ((heat\$4 or thermal\$4 or bak\$4) same (treat\$4 or convert\$4 or react\$4 or decomposition) same (oxygen or nitrogen or "N.sub.2" or "O. sub.2"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
20	31	(capacitor or (dielectric same top same bottom same electrode)) same (((photosensitive or organometallic) near5 sol\$3gel) or sol\$3gel or ((titanium or Ti or Al or alumin\$2m) same (organic near8 sol\$3gel))) same (mask or hard\$3mask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
21	55	(pattern\$4 same (capacitor or (dielectric same top same bottom same electrode))) and (((photosensitive or organometallic) near5 sol\$3gel) or sol\$3gel or ((titanium or Ti or Al or alumin\$2m) same (organic near8 sol\$3gel))) same (mask or hard\$3mask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

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22	10	((((photosensitive or organometallic) near5 sol\$3gel) or sol\$3gel or ((titanium or Ti or Al or alumin\$2m) near6 (organic near8 sol\$3gel))) same pattern\$4 same (hardmask or (hard near4 mask)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
23	27	((((photosensitive or organometallic) near5 sol\$3gel) or ((titanium or Ti or Al or alumin\$2m) near6 (organic near8 sol\$3gel))) same (pattern\$4 or hardmask or (hard near4 mask)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
24	4	((((photosensitive or organometallic) near5 sol\$3gel) or sol\$4gel or ((titanium or Ti or Al or alumin\$2m) near6 (organic near8 sol\$3gel))) same hardmask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
25	0	((((photosensitive or organometallic) near5 sol\$3gel) or sol\$4gel or ((titanium or Ti or Al or alumin\$2m) near6 (organic near8 sol\$3gel))) near14 ((etch\$5resistant near5 mask) or hardmask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
26	4	((((photosensitive or organometallic) near5 sol\$3gel) or sol\$4gel or ((titanium or Ti or Al or alumin\$2m) near6 (organic near8 sol\$3gel))) same ((etch\$5resistant near5 mask) or hardmask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

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27	55	((((photosensitive or organometallic) near5 sol\$3gel) or sol\$4gel or ((titanium or Ti or Al or alumin\$2m) near6 (organic near8 sol\$3gel)))) and ((etch\$5resistant near5 mask) or hardmask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
28	9	((((photosensitive or organometallic) near5 sol\$3gel) or sol\$4gel) same (layer or deposit\$4 or film or form\$3) same capacitor same (photoresist or resist) same pattern\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
29	16	((((photosensitive or organo\$4metallic) near7 sol\$3gel) or sol\$4gel) same ((titanium near4 alkoxide) or TiOEt or (Ti near4 alkoxide near4 acetate)) same (heat\$4 or thermal\$4 or bak\$4) same (oxygen or nitrogen))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
30	3	((((photosensitive or organo\$4metallic) near7 sol\$3gel) or sol\$4gel) same ((titanium near4 alkoxide) or TiOEt or (Ti near4 alkoxide near4 acetate)) same (heat\$4 or thermal\$4 or bak\$4) same (photolithograph\$6 or lithograph\$6 or photoresist or resist))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

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31	2	((photosensitive or organo\$4metallic) near7 sol\$3gel) or sol\$4gel) same ((titanium near4 alkoxide) or TiOEt or (Ti near4 alkoxide near4 acetate)) same (heat\$4 or thermal\$4 or bak\$4) same capacitor) and (photolithograph\$6 or lithograph\$6 or photoresist or resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
32	10	((photosensitive or organo\$4metallic) near7 sol\$3gel) or sol\$4gel) same ((titanium near4 alkoxide) or TiOEt or (Ti near4 alkoxide near4 acetate)) same (heat\$4 or thermal\$4 or bak\$4) same capacitor) and (photolithograph\$6 or lithograph\$6 or photoresist or resist or pattern\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

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33	4	<p>capacitor and</p> <p>((photosensitive near5 sol\$3gel) or organo\$4metallic or ((titanium or Ti) near7 sol\$3gel) or (Ti\$2Al near5 organic near4 gel) or (titanium near3 alumin\$3 near4 sol\$3gel) or TiOEt ) same</p> <p>(photoresist or resist or photo\$3cur\$4 or (radiation near5 sensitive)) same</p> <p>(pattern\$3 or expos\$3 or illuminat\$3 or irradiat\$3))</p> <p>and ((thermal\$3 near5 (decompos\$5 or treat\$5)) or heat\$4 or bak\$4) and (etch\$3 same pattern\$3 same ((hard near5 mask) or (etch\$3resist\$3 near5 mask\$3)))</p>	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
34	1	<p>430/330.cc1s. and capacitor</p> <p>and ((photosensitive near5 sol\$3gel) or ((titanium or Ti) near7 sol\$3gel) or (Ti\$2Al near5 organic near4 gel) or (titanium near3 alumin\$3 near4 sol\$3gel) or TiOEt or TEOS)</p> <p>same (photoresist or resist or photo\$3cur\$4 or (radiation near5 sensitive)) same</p> <p>(pattern\$3 or expos\$3 or illuminat\$3 or irradiat\$3))</p> <p>and ((thermal\$3 near5 (decompos\$5 or treat\$5)) or heat\$4 or bak\$4) and (etch\$3 same pattern\$3 same ((hard near5 mask) or (etch\$3resist\$3 near5 mask\$3)))</p>	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

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35	1	430/322.ccls. and capacitor and (((photosensitive near5 sol\$3gel) or ((titanium or Ti) near7 sol\$3gel) or (Ti\$2Al near5 organic near4 gel) or (titanium near3 alumin\$3 near4 sol\$3gel) or TiOEt or TEOS) same (photoresist or resist or photo\$3cur\$4 or (radiation near5 sensitive)) same (pattern\$3 or expos\$3 or illuminat\$3 or irradiat\$3)) and ((thermal\$3 near5 (decompos\$5 or treat\$5)) or heat\$4 or bak\$4) and (etch\$3 same pattern\$3 same ((hard near5 mask) or (etch\$3resist\$3 near5 mask\$3)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
36	1	430/320.ccls. and capacitor and (((photosensitive near5 sol\$3gel) or ((titanium or Ti) near7 sol\$3gel) or (Ti\$2Al near5 organic near4 gel) or (titanium near3 alumin\$3 near4 sol\$3gel) or TiOEt or TEOS) same (photoresist or resist or photo\$3cur\$4 or (radiation near5 sensitive)) same (pattern\$3 or expos\$3 or illuminat\$3 or irradiat\$3)) and ((thermal\$3 near5 (decompos\$5 or treat\$5)) or heat\$4 or bak\$4) and (etch\$3 same pattern\$3 same ((hard near5 mask) or (etch\$3resist\$3 near5 mask\$3)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

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37	6	<p>"430"/\$.ccls. and capacitor and (((photosensitive near5 sol\$3gel) or ((titanium or Ti) near7 sol\$3gel) or (Ti\$2Al near5 organic near4 gel) or (titanium near3 alumin\$3 near4 sol\$3gel) or TiOEt or TEOS) same (photoresist or resist or photo\$3cur\$4 or (radiation near5 sensitive)) same (pattern\$3 or expos\$3 or illuminat\$3 or irradiat\$3)) and ((thermal\$3 near5 (decompos\$5 or treat\$5)) or heat\$4 or bak\$4) and (etch\$3 same pattern\$3 same ((hard near5 mask) or (etch\$3resist\$3 near5 mask\$3)))</p>	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB